AMENDMENTS TO THE CLAIMS

1. (Canceled).

2. (Currently Amended) The monolithic multi-focal length refractive element as recited in Claim 5 [[1]], wherein a ~~the~~ value of an optical property for said first surface region is different from a value of said optical property for said second surface region.

3. (Original) The monolithic multi-focal length refractive element as recited in Claim 2 wherein said optical element blank comprises silica (SiO_2).

4. (Original) The monolithic multi-focal length refractive element as recited in Claim 2 wherein said optical element blank comprises gallium arsenide (GaAs).

5. (Currently Amended) ~~The monolithic multi-focal length refractive element as recited in Claim 1~~ A monolithic multi-focal length refractive element comprising:

a single monolithic optical element blank comprising:

a first surface region having a first characteristic radius of curvature; and

a second surface region having a second characteristic radius of curvature, wherein said monolithic multi-focal length refractive element has a maximum dimension of less than five millimeters.

6. (Currently Amended) The monolithic multi-focal length refractive element as recited in Claim 5 [[1]], wherein said monolithic

optical element blank comprises a third surface region having a third characteristic radius of curvature.

7-8. (Canceled).

9. (Currently Amended) ~~The method as recited in Claim 8~~ A method for making a multi-focal length refractive element, said method comprising:

forming in an optical element blank a first surface region characterized by a first radius of curvature by etching said optical element blank using a first etch process having a first etch selectivity; and

forming on said optical element blank a second surface region characterized by a second radius of curvature by ~~wherein said forming said second surface region comprises~~ etching said optical element blank using a second etch process having a second etch selectivity.

10. (Original) The method as recited in Claim 9 wherein said first etch selectivity is less than said second etch selectivity.

11. (Currently Amended) The method as recited in Claim 9 [[7]] additionally comprising forming a first shape transfer mask and etching said first shape transfer mask using said ~~a~~ first etch process.

12. (Currently Amended) The method as recited in Claim 11 additionally comprising etching said first shape transfer mask using said ~~a~~ second etch process.

13. (Currently Amended) The method as recited in Claim 11 [[13]] additionally comprising forming a second shape transfer mask.

14. (Currently Amended) The method as recited in Claim 13 additionally comprising using <u>said</u> ~~a~~ second etch process to etch said second shape transfer mask.

15-23. (Canceled).

24. (New) A method for making a multi-focal length refractive element, said method comprising:

forming in an optical element blank a first surface region characterized by a first radius of curvature;

forming on said optical element blank a second surface region characterized by a second radius of curvature;

forming a first shape transfer mask and etching said first shape transfer mask using a first etch process; and

etching said first shape transfer mask using a second etch process.

25. (New) The method as recited in Claim 24 wherein said forming said first surface region comprises etching said optical element blank using said first etch process having a first etch selectivity.

26. (New) The method as recited in Claim 25 wherein said forming said second surface region comprises etching said optical element blank using said second etch process having a second etch selectivity.

27. (New) The method as recited in Claim 26 wherein said first etch selectivity is less than said second etch selectivity.

28. (New) The method as recited in Claim 24 additionally comprising forming a second shape transfer mask.

29. (New) The method as recited in Claim 28 additionally comprising using said second etch process to etch said second shape transfer mask.